EAST Search History

Ref#	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S3	4	(("5,314,569") or ("6,346,189")).PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/11/25 09:16
S7	2	("20020136681").PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/11/25 09:19
S8	2	("20060292870").PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/11/25 12:02
S9	30	(calibrated pore\$1)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/25 13:27
S12	66	(PRIBAT, DIDIER).in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/25 15:49
S13	4	(WEGROWE, JEAN-ERIC).in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/25 15:49
S14	10	(WADE, TRAVIS).in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/25 15:49
S15	8	(WEGROWE).in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/25 15:54

S17	804	(single crystal\$4 or single- crystal\$4) near2 zone	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/25 17:03
S18	79	(single crystal\$4 or single- crystal\$4) near2 zone and (alumina or aluminium oxide)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/25 17:03
S29	270	(epitax\$5) and ((electrochemical or electro- chemical or electroplating or electro-plating) near2 (growth or deposition)) and (aluminium) and (cobalt)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/26 10:40
S33	975	alumina and nanoporous	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/26 13:19
S36	371	(alumina or sapphire or aluminium oxide) and nanoporous and (nanowire or nanotube or nanorod)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/26 13:21
S37	2	("6,359,288").PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/11/26 13:39
S40	1	(anodic oxidation) and (single crystal aluminium substrate) and (alumina or aluminium oxide or sapphire)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/26 13:51
S41	1	(anodic oxidation) and (single crystal near2 aluminium substrate) and (alumina or aluminium oxide or sapphire)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/26 13:52
S42	1	(anodic oxidation) and (single crystal near4 aluminium substrate) and (alumina or aluminium oxide or sapphire)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/26 13:52

S43	1	(anodic oxidation) and (single crystal near4 aluminium near2 substrate) and (alumina or aluminium oxide or sapphire)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/26 13:53
S44	1	(anodic oxidation) and (single crystal near4 aluminium near4 substrate) and (alumina or aluminium oxide or sapphire)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/26 13:53
S45	4	(anodic oxidation) and (single crystal same aluminium near4 substrate) and (alumina or aluminium oxide or sapphire)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/26 13:53
S47	2	(anodic oxidation or anodization) and (single crystal near4 aluminium near4 substrate) and (alumina or aluminium oxide or sapphire)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/26 13:54
S48	19	(anodic oxidation or anodization) and (single crystal near4 aluminium) and (alumina or aluminium oxide or sapphire)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/26 13:56
S49	12	(anodic oxidation or anodization) and (single crystal aluminium)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/26 14:01
S50	37	(advantage\$1 or benifit\$1) same (single crystal aluminium)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/26 15:25
S51	5	("3929527" "4325776" "4554030" "5216271" "5262361").PN. OR ("5782997").URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/11/26 15:27
S53	10	(advantage\$1 or benifit\$1) same (single crystal substrate) and (anodic)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 07:30

S54	632	(advantage\$1 or benifit\$1) same (single crystal substrate) NOT S53	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 07:34
S55	2	single crystal aluminium substrate	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 07:35
S62	886	((carbon nanotubes) or (nanowires)) and (porous) and catalyst and (aluminium or aluminum) and (@ad<"20041012" or @rlad<"20041012")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 08:42
S63	17	S62 and diffusion barrier	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 09:03
S64	129	S62 and electroplating	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 09:08
S66	148	S62 and (chemical vapor deposition with catalyst)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 09:08
S67	14	single crystal aluminium and monocrystalline silicon	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 09:23
S69	385	aluminium (deposition or thin film or metal film) and (monocrystalline or mono- crystalline or single crystal or single-crystal) (silicon or substrate)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 09:33

S70	310	aluminium (deposition or thin film or metal film) and (monocrystalline or monocrystalline or single crystal or single-crystal) (silicon or substrate) and (@ad< "20031013")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 09:34
S71	325	S62 and barrier	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 09:41
S72	48	S62 and barrier same catalyst	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 09:42
S73	1644	((carbon nanotubes) or (nanowires) or nanorods) and (porous or nanoporous or nano-porous) and catalyst and (@ad<"20041012" or @rlad<"20041012")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 09:43
S74	37	S73 and barrier with catalyst	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 09:43
S80	20	((anneal or annealed or annealing) same catalyst) and (magnetic field) and (carbon nanowire or nanotube) and (@ad<"20031013") NOT drug NOT skin NOT inkjet	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 10:53
S81	20	"6,894,359"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 12:33
S84	101	nanotube and nanoporous and transistor and (@ad< "20031013" or @rlad< "20031013")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 12:35

S85	2	("7,189,435").PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/12/01 12:40
S87	2	("20020158342").PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/12/01 12:40
S88	234	S73 and (chemical vapor deposition with (catalyst or cobalt))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 14:18
S101	712	silicon same diffusion same aluminium same titanium nitride same barrier and (@ad< "20031013")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 15:17
S107	1647	((carbon nanotubes) or (nanowires) or nanorods) and (porous or nanoporous or nano-porous) and catalyst and (@ad<"20041012" or @rlad<"20041012")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/02 08:44
S108	1	S107 and (chemical vapor deposition with (catalyst or cobalt) with bottom with pore)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/02 08:44
S109	5	S107 and ((chemical vapor deposition or CVD) with (catalyst or cobalt or Co) with bottom with pore)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/02 08:45
S110	25	S107 and ((chemical vapor deposition or CVD) with (catalyst or cobalt or Co) with (bottom or pore))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/02 08:46
S111	42	carbonyl metal and catalyst and chemical with deposition	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/02 08:57

S112	2	("5102647").PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/12/02 09:05
S113	1060	cobalt with chemical with deposition	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/02 09:23
S114	7	cobalt with pore with chemical with deposition	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/02 09:23
S118	16	cobalt same pore with chemical with deposition NOT S114	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/02 09:47
S120	102	cobalt and pore with chemical with deposition NOT S114 NOT S118	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/02 09:48
S121	83	cobalt and pore with chemical with (vapor or gas) with deposition NOT S114 NOT S118	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/02 09:48
S122	2	("6362011").PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/12/02 09:49
S128	67	nanowire and catalyst and alumina and (nanopore or nanoporous) and (@AD< "20041012")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/02 14:42
S129	10	(("4,472,533") or ("5,174,883") or ("5,198,112") or ("5,202,290") or ("5,581,091,")).PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/12/02 14:49

S134	238	(977/843).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2009/06/04 14:30
S135	19	(977/893).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2009/06/04 14:30
S136	8	("5322196" "6146227" "6597090" "6627842" "6827979" "7002820" "7189940" "7419887").PN. OR ("7538015").URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2009/06/04 15:05
mS137	18	("20010028872" "20020114949" "20020117659" "20020130311" "20020172820" "20020175408" "20020178846" "20030089899" "20030132461" "20040033339" "20040043208" "20060032526" "5997958" "6231744" "6278231" "6359288" "6401526" "6709929").PN. OR ("7348670").URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2009/06/04 15:21
S138	21	(Os! or Osmuim) with barrier with (Co or cobalt) with (Si or silicon)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2009/06/05 10:13
S139	50	(Os! or Osmuim) with barrier with (Si or silicon)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2009/06/05 10:40
S140	82	cvd with cobalt with catalyst	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2009/06/05 11:46
S141	3	catalyst precurser and cobalt	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2009/06/05 11:56

S144	70	carbonyl same cvd and nanotube	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2009/06/05 12:03
S145	1561	nanotube and FET	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2009/06/05 12:37
S146	1413	carbon nanotube and FET	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2009/06/05 12:37
S147	187	carbon nanotube and FET and template	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2009/06/05 12:37
****S148	9	("20020153160" "20030148562" "20030175591" "20030178601" "20030179559" "20040004235" "20040149979" "20040224490" "20040233649" "20040233649" "20050012163" "20050029654" "20050051805" "20050056826" "20050056826" "200500145838" "20050145838" "20050156203" "20050156203" "6423583" "6465813" "6566704" "6590231" "677098" "6740910" "6759693" "6798000" "6809361" "6815294" "6830981" "6833567" "6866891" "6891227" "6927982" "7265376").PN. OR ("7462890").URPN.	US-PGPUB; USPAT; USOCR	ADJ		2009/06/05

S149	6	US-6914256-\$.DID. OR US-20070113779-\$.DID. OR US-20050276743-\$.DID. OR US-20050156180-\$.DID. OR US-20040144985-\$.DID. OR US-20030215865-\$.DID.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2009/06/05 14:34
S151	252	(977/932).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2009/06/05 16:15
S152	89	(977/936).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2009/06/05 16:15
S153	126	(977/937).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2009/06/05 16:15
S154	108	(977/938).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2009/06/05 16:15
S155	26	electrode with extension with pore	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2009/06/05 17:00
S156	0	gate with extension with pore	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2009/06/05 17:10
S157	0	gate with extension with nanopore	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2009/06/05 17:10
S158	0	gate with (extension or extending) with nanopore	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2009/06/05 17:10
S159	33	gate with nanopore	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2009/06/05 17:10
S161	33	gate same nanopore not S159	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2009/06/05 17:32
S162	2	(("5,581,091") or ("6,034,468")).PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2009/06/05 17:33

S165	107	nanotube and fet and	US-PGPUB;	ADJ	ON	2009/06/05
		(@ad< "20040101") and (AAO	USPAT; USOCR;			17:55
		or aluminium oxide or	FPRS; EPO;			
		alumina)	JPO;			
		,	DERWENT;			
			IBM_TDB			

6/6/2009 8:57:50 AM

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